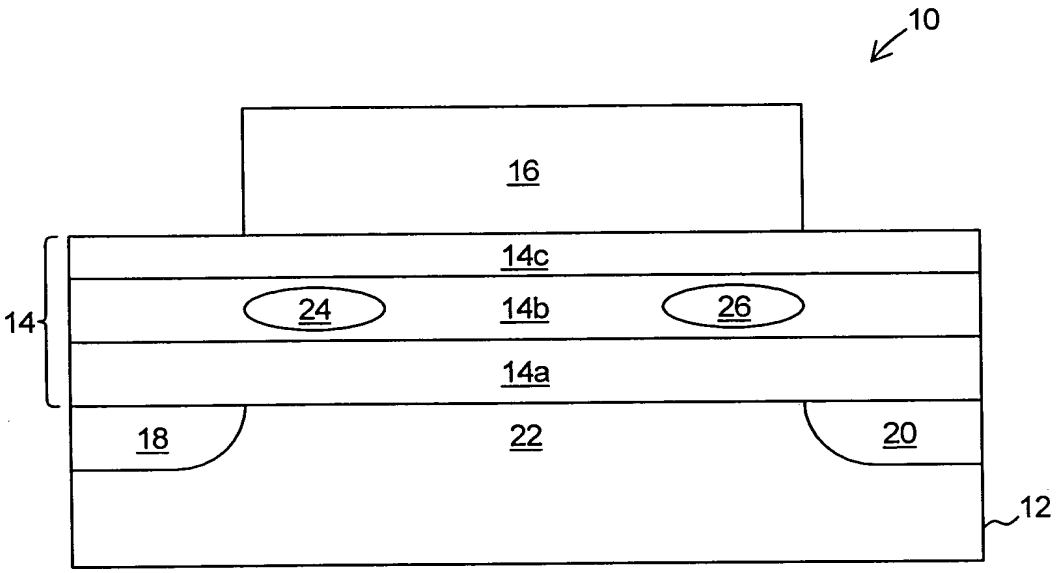

Figure 1

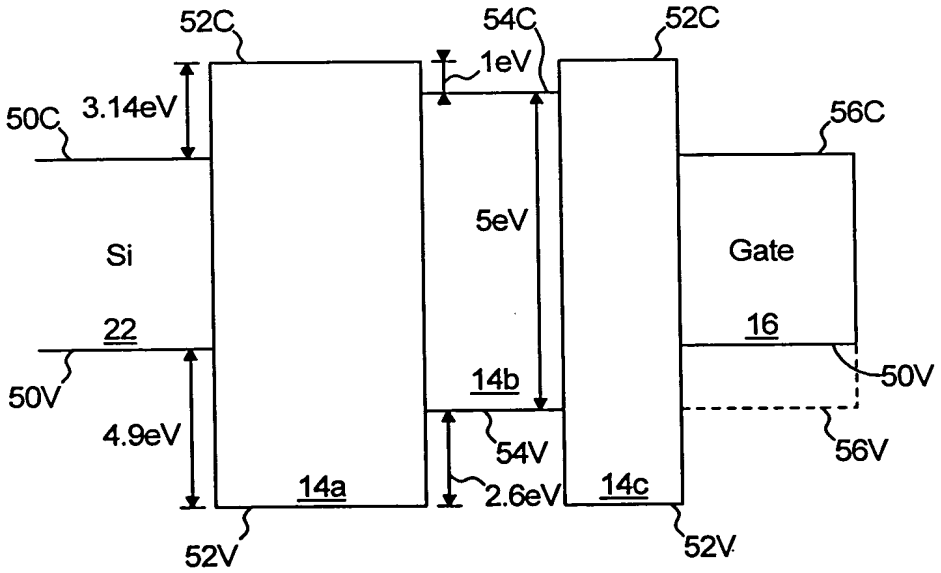

Figure 2a

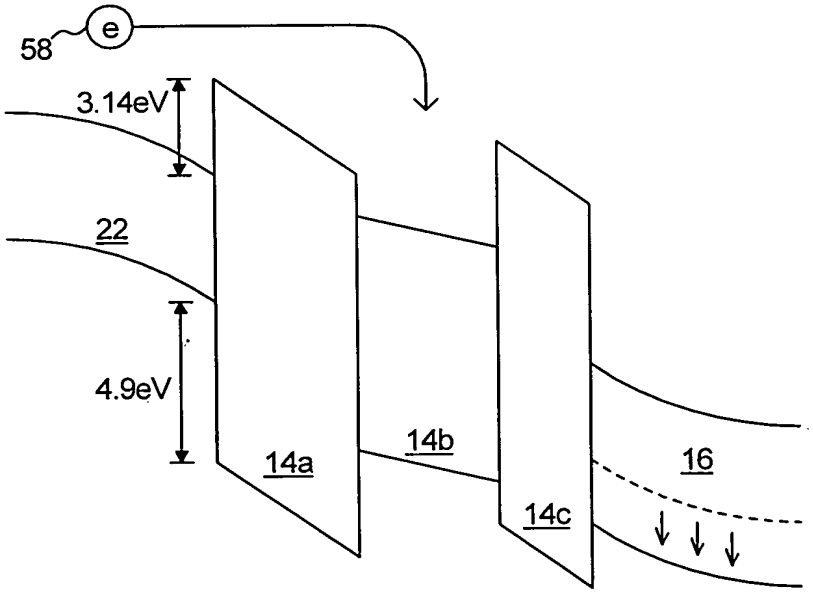

Figure 2b

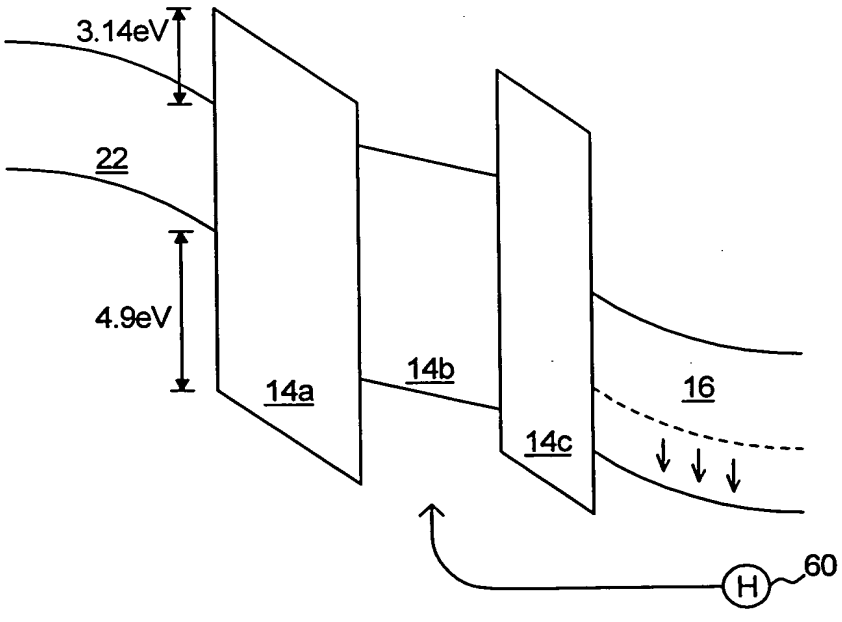

Figure 2c

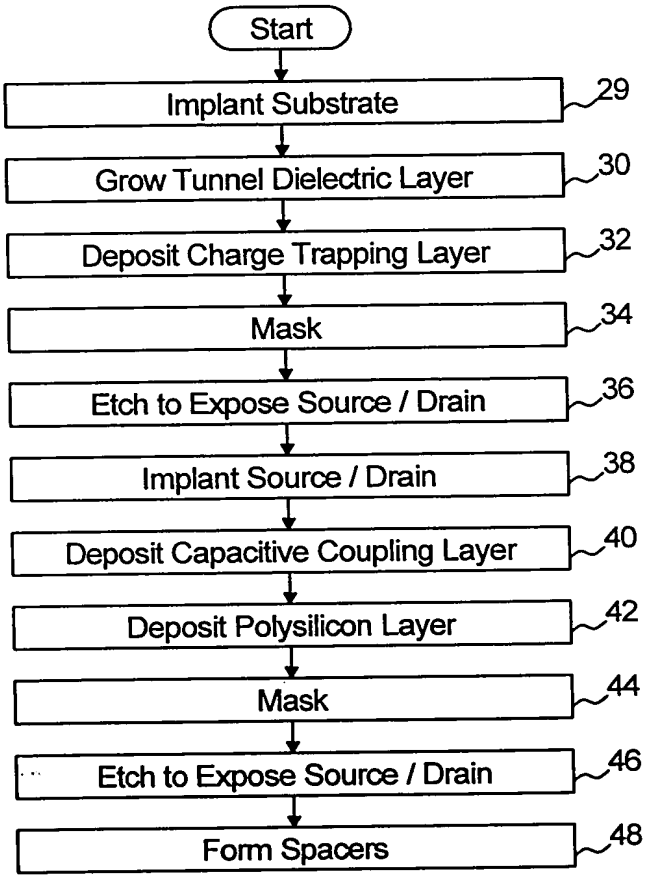
Start
Implant Substrate
29
Grow Tunnel Dielectric Layer
30
Deposit Charge Trapping Layer
32
Mask
34
Etch to Expose Source / Drain
36
Implant Source / Drain
38
Deposit Capacitive Coupling Layer
40
Deposit Polysilicon Layer
42
Mask
44
Etch to Expose Source / Drain
46
Form Spacers
48

Figure 3

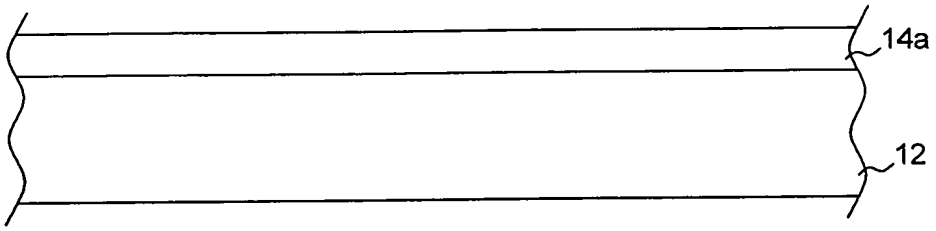

Figure 4a

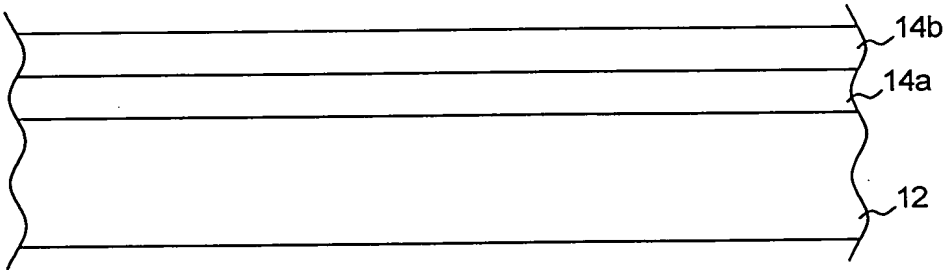

Figure 4b

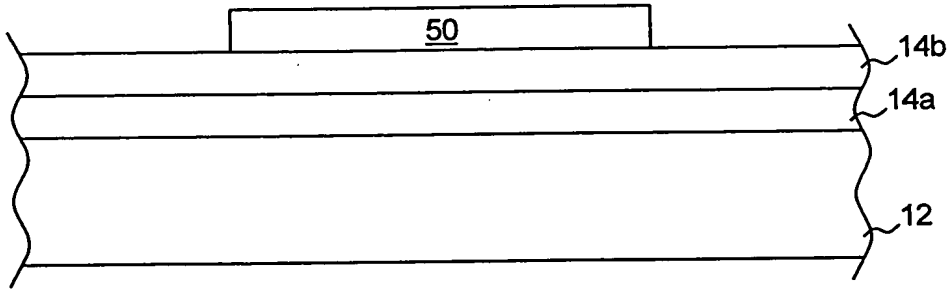

Figure 4c

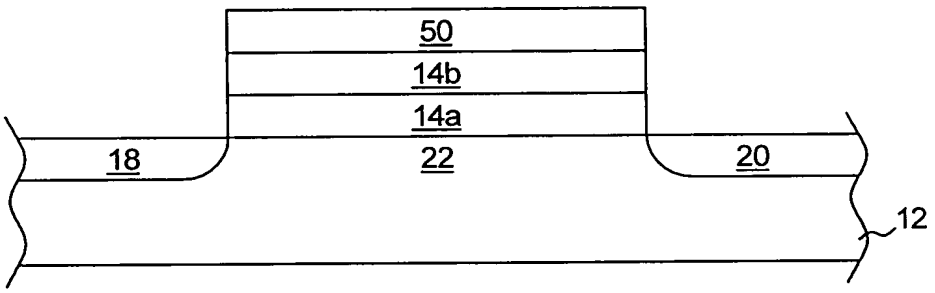

Figure 4d

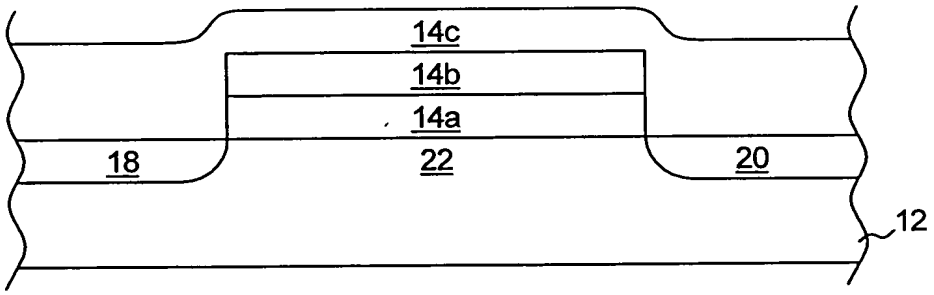

Figure 4e

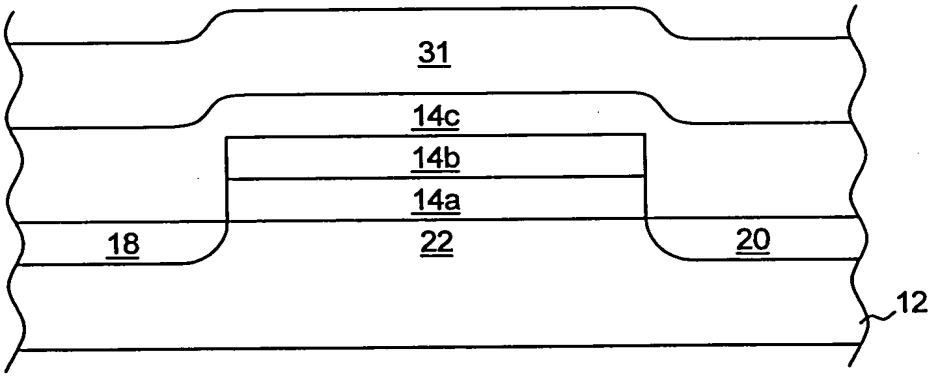

Figure 4f

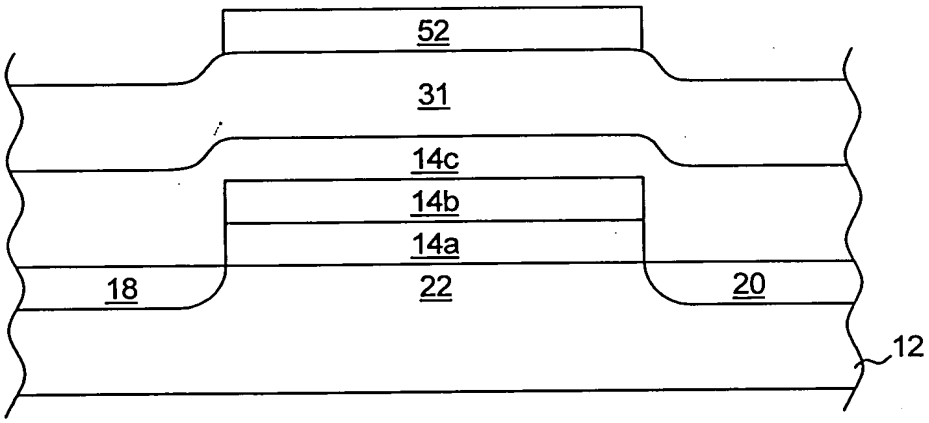

Figure 4g

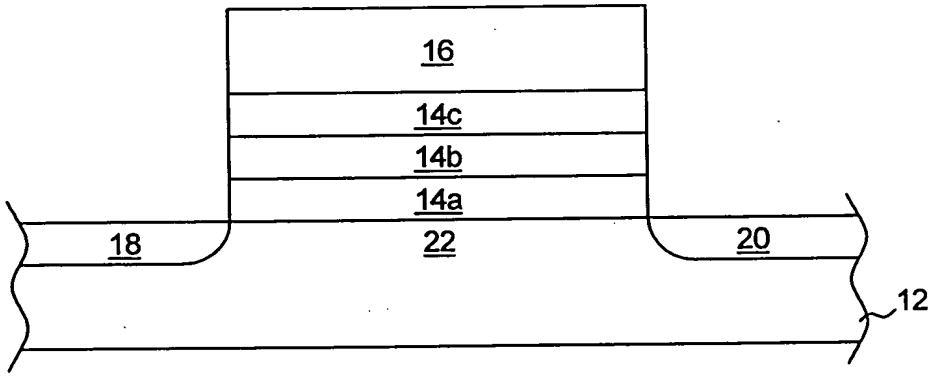

Figure 4h